

ABSTRACT

An exposure apparatus is provided in which, even when a projection optical system and substrate are in close proximity, collisions between the projection optical system and the substrate or the substrate stage can be easily avoided. An exposure apparatus EX having a projection optical system (30) which projects and transfers a pattern (PA) formed on a mask (R) onto a substrate (W), and a substrate stage (42), positioned below the projection optical system (30), which moves in directions substantially perpendicular to the direction of the system (30), which moves in directions substantially perpendicular to the direction of the optical axis (AX) of the projection optical system (30) while supporting the substrate (W), comprises a detector (81), positioned on the outer periphery of the projection optical system (30), and which detects the position of the substrate stage (42) or substrate W along the direction of the optical axis (AX), and a control device (70), which based on the detection results of the detector (81), stops or reverses the movement of the substrate stage (42).